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Laboratory of Advanced Science and Technology for Industry, University of Hyogo
3-1-2 Kouto, Kamigori-cho, Ako-gun, Hyogo, 678-1205 JAPAN
TEL: +81-791-58-0249 / FAX: +81-791-58-0242

Editor in Chief
Editors

Shuji Miyamoto
Masahito Niibe
Yoshihiko Shoji
Kazuhiro Kanda
Yuichi Utsumi
Takeo Watanabe

Cover photograph **Dual Grating Interferometric Exposure Tool**

The exposure tool consists of a main chamber which includes wafer stage and diffraction gratings. And a load lock chamber is attached to the exposure chamber to exchange a wafer. It is believed that the developed EUV interference lithographic system is a beneficial tool to develop EUV resist which satisfies the specification of 22 nm and beyond.

